

## IR - Sadtler Polymers & Monomers (Subset) 2 - Wiley

Spectra - 1,705

### Description

This database contains 1,705 monomers, polymers and precursors commonly encountered in both industry and academia to provide a broad base for solving polymer and plastic analytical problems. It includes many classic compounds, which makes it particularly useful as a reference. Analytical applications include identification, quality control, deterioration studies, and materials selection.

### Additional Information

Each compound is identified by its commercial or trade name. The following additional information will also be supplied when available: chemical composition, source of sample, technique, and classification.

### Classifications

#### Polymers

Paraffins  
Polyethylenes  
Polybutenes  
Polypropylenes  
Polybutadienes  
Polyisoprenes  
Coumarone-Indene Resins  
Polyterpenes  
Polystyrenes  
Fluorinated Hydrocarbons  
Chlorinated Hydrocarbons  
Silicones  
Polyurethanes & Urethane Prepolymers  
Acetals  
Polyethers

Thioplasts  
Anhydride Polymers  
Cellulosics  
Epoxy Resins  
Vinyl Polymers & Copolymers  
Phenolic Resins  
Polyacrylic Acids & Salts  
Acrylic and Methacrylic Polymers  
Polyesters  
Rosins & Polymerized Fats  
Aminoplasts  
Polyamides, Polyimides, & Polyimines  
Polyvinylpyrrolidones  
Polyvinylpyridines  
Ion Exchange Resins  
Polymers containing Sulfur

#### Monomers and Precursors

Compounds containing Halogen  
Compounds containing Phosphorous  
Alcohols & Phenols  
Compounds containing Sulfur  
Acrylates and Methacrylates  
Amines  
UV Light Absorbers  
Amides  
Compounds containing Nitrile  
Miscellaneous Carboxylic Acid Esters  
Carboxylic Acids  
Anhydrides  
Carboxylic Acid Chlorides  
Aldehydes, Ketones, Oximes, & Quinones  
Phthalates  
Aromatic Hydrocarbons  
Oxides & Peroxides  
Organometallics

*This collection has been subject to the Sadtler Data Review Protocol™ to provide you with the highest standard in spectral data today. These rigorous qualifying procedures start at data acquisition and continue throughout the database development process.*